

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4470	((phas\$3 or shift\$3) near2 (mask or photomask or reticle) or PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:30
L2	803	1 and ((attenuat\$3 or halftone or half tone) with (phas\$3 or shift\$3 or PS or PSM) or attPSM or att PSM or HPSM or H PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:31
L3	222	2 and ((etch\$3 or groov\$3 or recess\$3 or mesa or rais\$3 or thick\$4) with (phas\$3 or shift\$3 or PS or PSM) or attPSM or att PSM or HPSM or H PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:32
L4	98	3 and ((blank or wavelength or wave length) with (phas\$3 or shift\$3 or mask or photomask or reticle or PS or PSM) or attPSM or att PSM or HPSM or H PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:33
L5	8605	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:34
L6	422	216/12.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:35
L7	55	3 and (5 or 6) not 4	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:35
L8	238	2 and (5 or 6) not 4 not 7	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:35
L9	11	8 and (reactive ion near2 etch\$3 or RIE) with ("SF.sub.6" or "CF.sub.4" or sulfur hexafluoride or carbon tetrafluoride)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:36
L10	1	2 and (reactive ion near2 etch\$3 or RIE) with ("SF.sub.6" or "CF.sub.4" or sulfur hexafluoride or carbon tetrafluoride) not 4 not 7 not 9	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:39
L11	2	3 and ((blank or wavelength or wave length) with (phas\$3 or shift\$3 or mask or photomask or reticle or PS or PSM) or attPSM or att PSM or HPSM or H PSM) not 4 not 7 not 9 not 10	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:41

## EAST Search History

L12	1	3 and ((second or third or plural or multiple) with (wavelength or wave length or thick\$4) same (phas\$3 or shift\$3 or mask or photomask or reticle or PS or PSM) or attPSM or att PSM or HPSM or H PSM).ti,ab. not 4 not 7 not 9 not 10 not 11	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:42
L13	4	3 and ((second or third or plural or multiple) same (wavelength or wave length or thick\$4) same (phas\$3 or shift\$3 or PSM) or attPSM or att PSM or HPSM or H PSM).ti,ab. not 4 not 7 not 9 not 10 not 11 not 12	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:43
L14	5	2 and ((second or third or plural or multiple) same (wavelength or wave length or thick\$4) same (phas\$3 or shift\$3 or PSM) or attPSM or att PSM or HPSM or H PSM).ti,ab. not 4 not 7 not 9 not 10 not 11 not 12 not 13	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:43
L15	126	2 and ((second or third or plural or multiple) same (wavelength or wave length or thick\$4) same (phas\$3 or shift\$3 or PSM) or attPSM or att PSM or HPSM or H PSM) not 4 not 7 not 9 not 10 not 11 not 12 not 13 not 14	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:52
L16	70	15 and ((transmi\$6 or transpar\$6) same ((attenuat\$3 or halftone or half tone) same (phas\$3 or shift\$3 or PSM)) or attPSM or att PSM or HPSM or H PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:45
L17	7	((Cheng Ming or ChengMing) near2 Lin).in. not 4 not 7 not 9 not 10 not 11 not 12 not 13 not 14 not 16	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 10:53
L18	565	(5 or 6) and (attenuat\$3 or halftone or half tone or semitranspar\$6 or semitransmi\$6 or semi (transpar\$6 or transmi\$6) or partial\$2 (transpar\$6 or transmi\$6) or attPSM or att PSM or HPSM or H PSM).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 11:19
L19	22	18 and ((wavelength or wave length) and (thick\$4 or depth)).ti, ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 11:20
L20	57	18 and (wavelength or wave length).ti,ab. not 19	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 11:24

## EAST Search History

L21	144	18 and (transmit\$5 or transmis\$6 or transparen\$3) same (equation or expression or formula)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 11:24
L22	154	18 and (phas\$3 or shift\$3 or PS) same (equation or expression or formula)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 11:25
L23	112	21 and 22	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 11:25
L24	18	(mask or photomask or reticle or PSM) near3 blank same (different or other or another or plural or multiple) near3 (company or organization or corporation or enterprise or establishment or firm or outfit or crafter or business or fabricator or creator or builder or producer or assembler or manufacturer or maker or supplier)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 11:26
L25	0	((phas\$3 or shift\$3) near2 (mask or photomask or reticle) or PSM) and (attenuat\$3 or halftone or half tone or attPSM or att PSM or HPSM or H PSM) and (wavelength or wave length) and blank and etch\$3 and (transmit\$5 or transmis\$6 or transparen\$3) and (light\$3 or radiat\$3) and thickness and (company or organization or corporation or enterprise or establishment or firm or outfit or crafter or business or fabricator or creator or builder or producer or assembler or manufacturer or maker or supplier) ).clm.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 11:28
L26	8	((phas\$3 or shift\$3) near2 (mask or photomask or reticle) or PSM) and (attenuat\$3 or halftone or half tone or attPSM or att PSM or HPSM or H PSM) and (wavelength or wave length) and blank and etch\$3 and (transmit\$5 or transmis\$6 or transparen\$3) and (light\$3 or radiat\$3) and thickness ).clm.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/01/18 11:35